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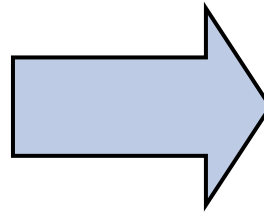
High-precision GD-MS analysis of Nickel super-alloys: major components and ultra-trace metals

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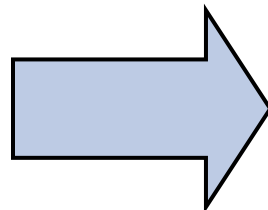
What is a DC-GDMS good for?



Analysis of conductive and semi conductive samples



What is a DC-GDMS good for?



- Analysis of ultra-trace to matrix elements
- Sputtering and ionization are separated processes \Rightarrow only minimal matrix effects \Rightarrow semi-quantitative analyses without calibration

[ppb]				Sample #1	Sample #2
Isotope	Mass	Resolution	Calibration	Conc. [ppb]	Conc. [ppb]
Na23(LR)	23	LR	STD RSF	1.1	1.2
Mg24(MR)	24	MR	Cal	0.50	0.57
Al27(MR)	27	MR	Cal	0.67	7.79
Si28(MR)	28	MR	Cal	32	14
P31(MR)	31	MR	Cal	1.7	2.3
Cl35(MR)	35	MR	STD RSF	408	485
K39(HR)	39	HR	STD RSF	1.8	1.2
Ca44(MR)	44	MR	STD RSF	2.4	4.2
Sc45(MR)	45	MR	STD RSF	0.07	0.01
Ti48(MR)	48	MR	Cal	4.7	1.7
V51(MR)	51	MR	STD RSF	0.04	0.10
Cr52(MR)	52	MR	Cal	0.41	0.37
Mn55(MR)	55	MR	Cal	0.06	0.08
Fe56(MR)	56	MR	Cal	0.36	0.77
Ni58(MR)	58	MR	Cal	0.40	0.58
Co59(MR)	59	MR	Cal	0.10	0.07
Zn68(MR)	68	MR	Cal	3.8	5.2
Ga69(MR)	69	MR	STD RSF	0.43	0.40
Ge74(HR)	74	HR	STD RSF	3.4	3.5
As75(MR)	75	MR	Cal	1.9	0.9
Se77(MR)	77	MR	Cal	15	20
Br79(MR)	79	MR	STD RSF=1	2.8	2.4
Rb85(MR)	85	MR	STD RSF=1	0.06	0.07
Sr88(LR)	88	LR	STD RSF	0.07	0.10
Y89(MR)	89	MR	STD RSF	0.06	0.06
Zr90(MR)	90	MR	Cal	0.18	0.20
Nb93(MR)	93	MR	STD RSF	0.02	0.07
Mo97(MR)	97	MR	STD RSF	0.71	0.64
Ru102(HR)	102	HR	STD RSF	0.52	0.81
Rh103(HR)	103	HR	STD RSF	9.4	7.4

Critical revision of GD-MS, LA-ICP-MS and SIMS as inorganic mass spectrometric techniques for direct solid analysis

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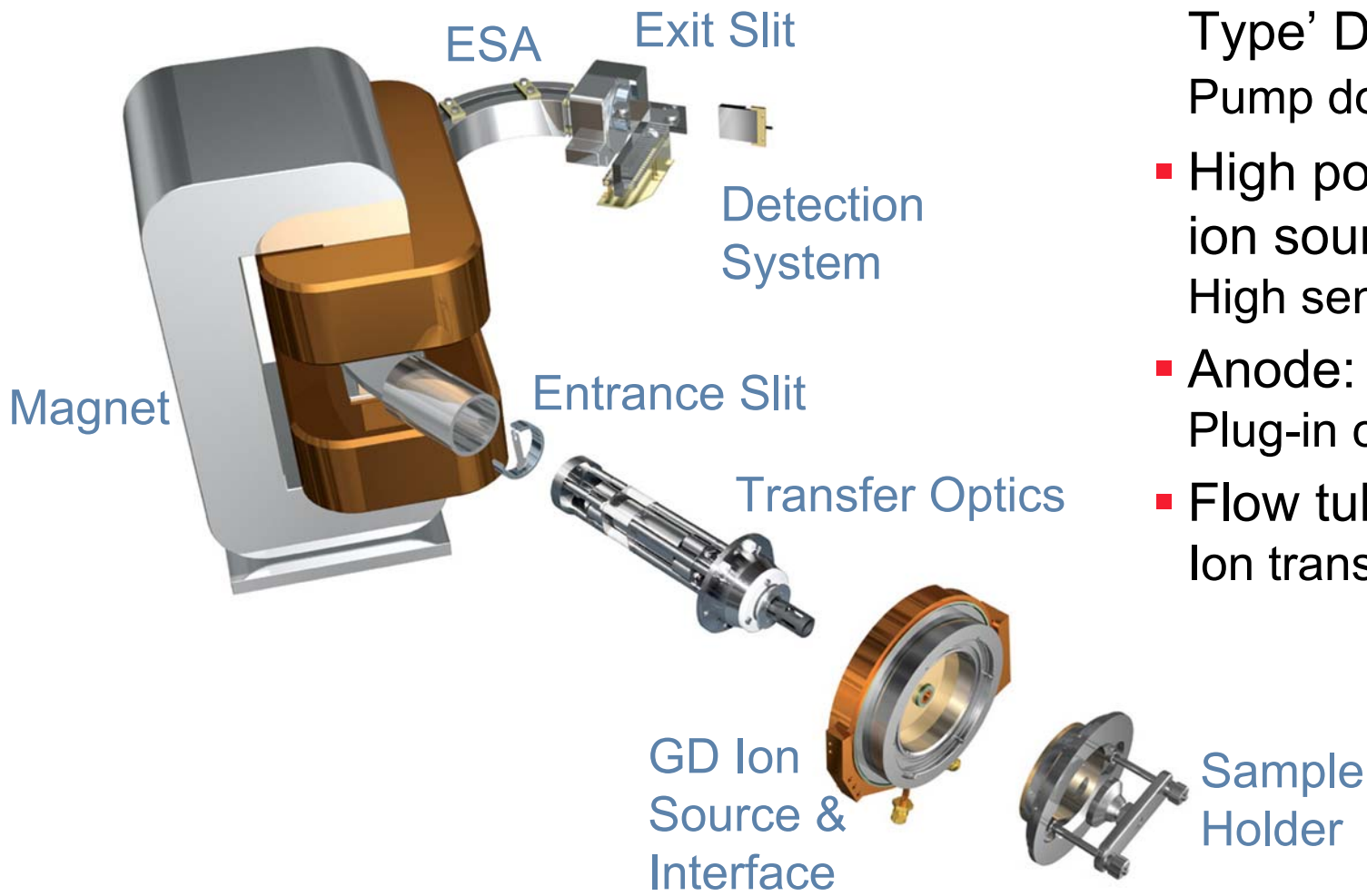
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General capabilities. The application of glow discharge devices as primary spectrochemical sources for direct solid elemental analysis in mass spectrometry is increasing because they offer several important advantages, such as a high depth resolution (\sim nm), fast sputtering rate (in the order of $\mu\text{m}/\text{min}$), multi-element capabilities (most of the elements of the periodic table can be determined), isotopic information in a relatively simple spectrum, low matrix effects, low limits of detection (in the range of $\mu\text{g}/\text{g}$ -ng/g), and ease of use.

Absolute and relative sensitivity factors for quantification. The low matrix dependence of GD-MS in comparison with other solid state analytical techniques provides absolute sensitivity factors which are matrix independent in a first approximation.

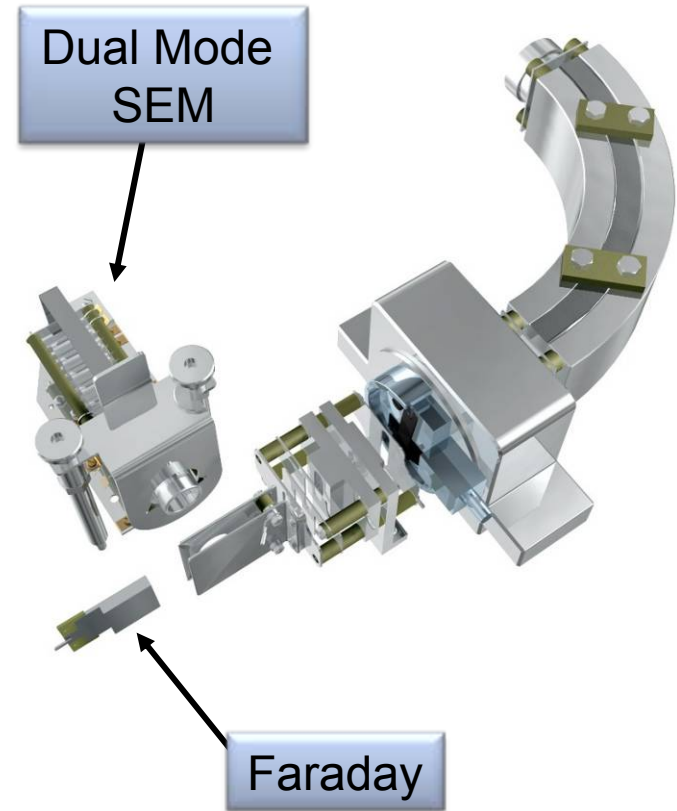
Components of the Element GD



- Similar to 'Grimm Type' DC source:
Pump down in 10s
- High power, fast flow ion source:
High sensitivity
- Anode:
Plug-in cap
- Flow tube:
Ion transport to MS

Requirements on detection system for GD

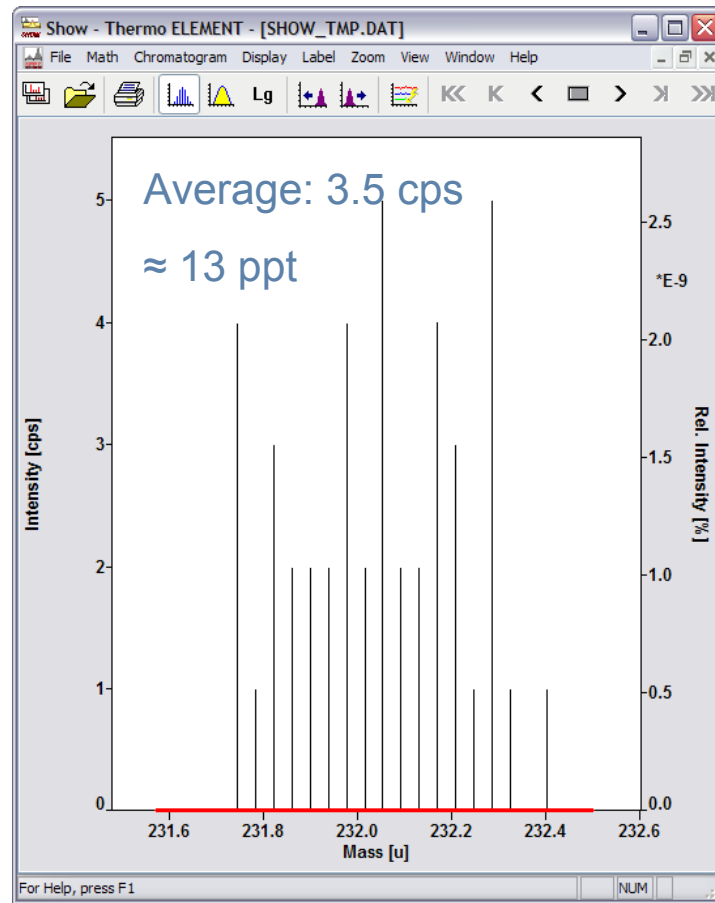
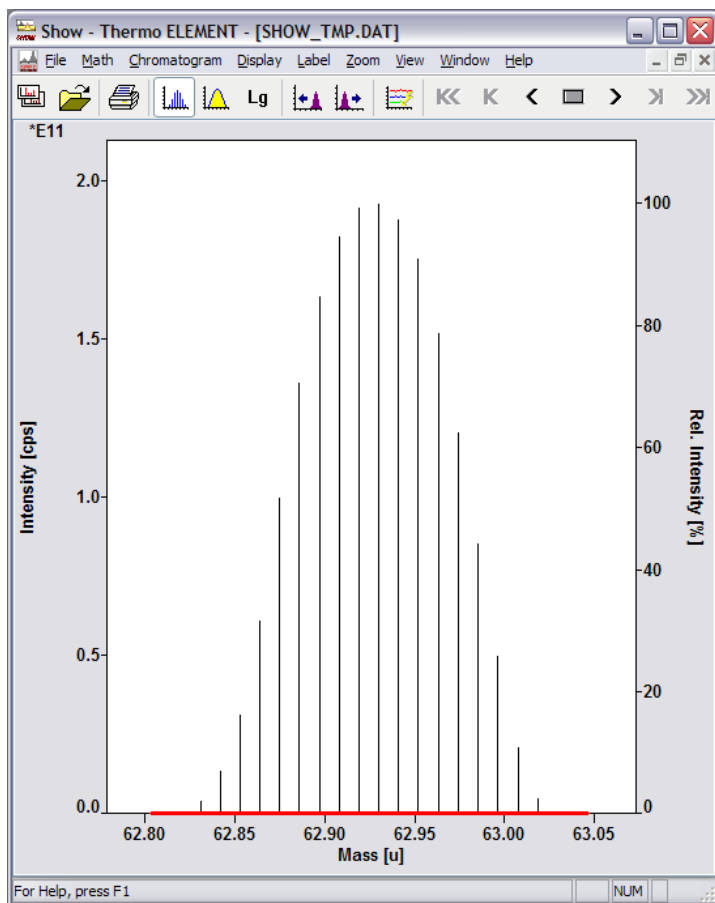
- High dynamic range
 - From <ppb to 100% matrix, i.e. > 12 orders of magnitude
 - Total ion current used for evaluation
 - Low noise
- Linear
 - Semi quantitative results without standards
 - Calibration at higher concentrations than the samples possible



Detection Power (Th in Copper, Low Resolution)

Theor. Detection Limit:

$2 \cdot 10^{11}$ cps Signal @ 0.2 cps Noise :DL_{theor.} : 1 ppt



Integration time per sample: 100 ms Th, 1 ms Cu; 20 samples per peak; 10 Spectra

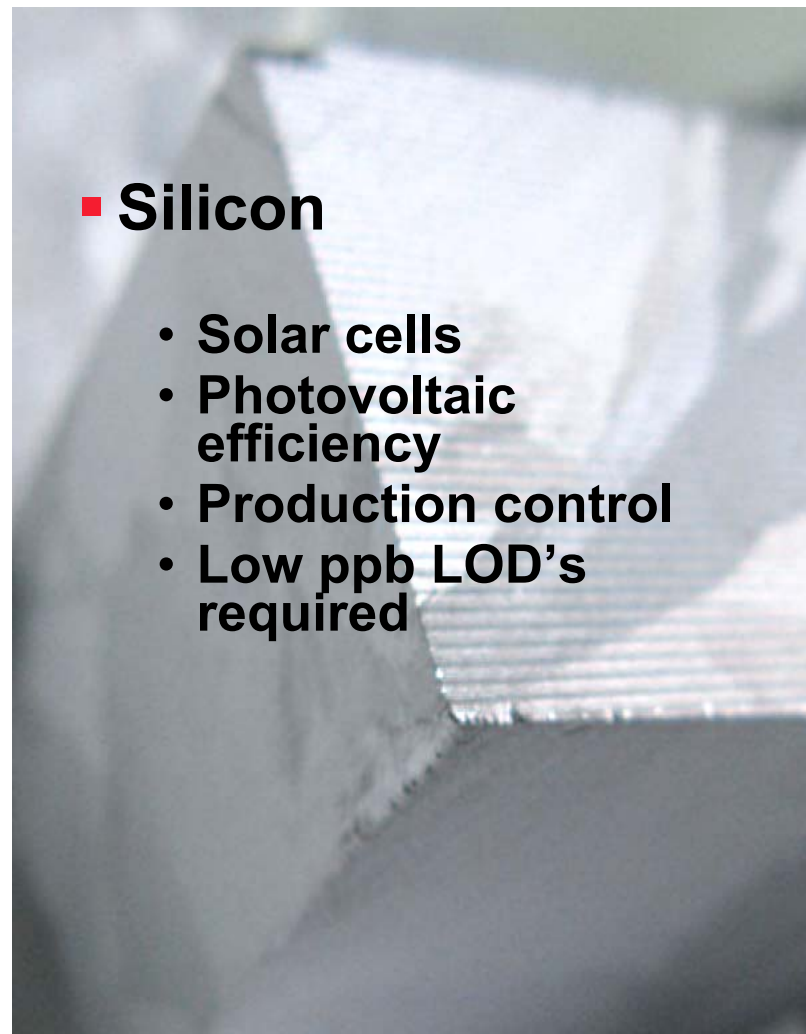
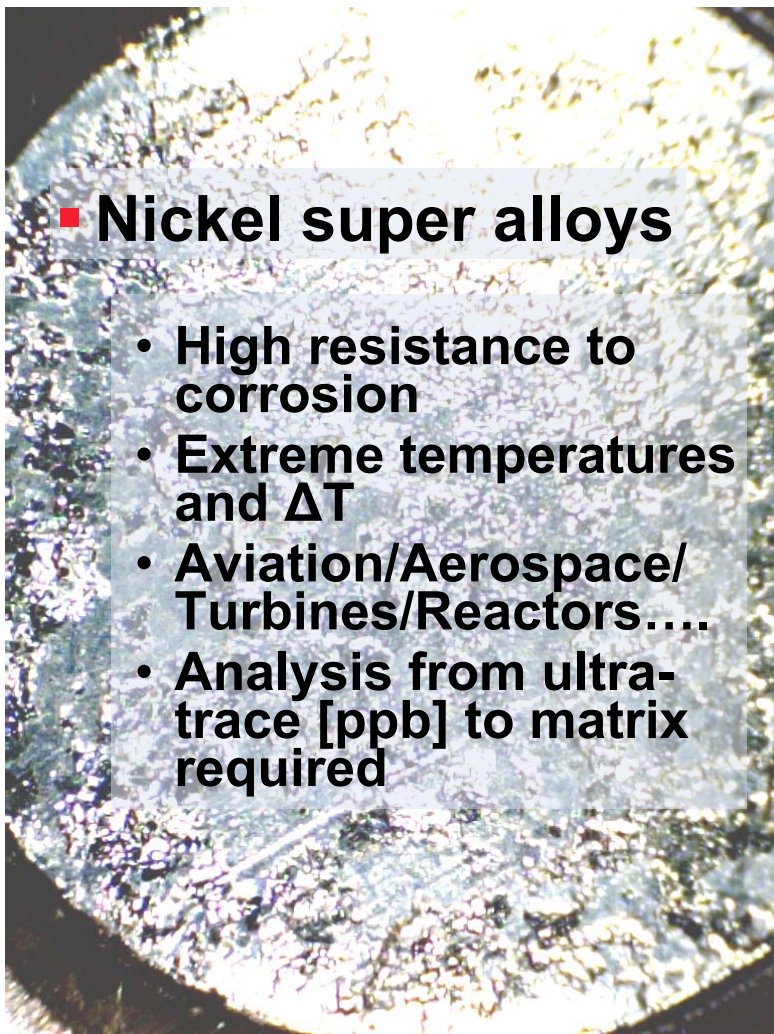
Applications...

- Overview
- Use of detection system: Analysis of Ni-Alloys (“Super-Alloys”)
- Low detection limits: solar silicon
- Special aspects of solid sampling at ppb level

Overview: sample matrices

H																	He
Li	Be											B	C	N	O	F	Ne
Na	Mg											Al	Si	P	S	Cl	Ar
K	Ca	Sc	Ti	V	Cr	Mn	Fe	Co	Ni	Cu	Zn	Ga	Ge	As	Se	Br	Kr
Rb	Sr	Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	Cd	In	Sn	Sb	Te	I	Xe
Cs	Ba	La	Hf	Ta	W	Re	Os	Ir	Pt	Au	Hg	Tl	Pb	Bi	Po	At	Rn
Fr	Ra	Ac															
			Ce	Pr	Nd	Pm	Sm	Eu	Gd	Tb	Dy	Ho	Er	Tm	Yb	Lu	
			Th	Pa	U	Np	Pu	Am	Cm	Bk	Cf	Es	Fm	Md	No	Lr	

Application examples



Application examples Ni Alloys

Challenges

- Reliable and routine determination from matrix to ultratrace elements
- Industrial production control
- Large number of alloy components
- Precise calibration with CRM
- Most important: soft metals at ppm/sub-ppm level strongly deteriorate alloy quality



Repeat GD-MS analysis of NIST 1249 (Inconel 718)

Element	Unit	Spot 1	Spot 2	Spot 3	Spot 4	Spot 5	Spot 6	Spot 7	Spot 8	Spot 9	Spot 10
Ni	[%]	56.9	56.7	57.2	57.8	57.7	57.5	56.9	57.6	57.3	56.9
Fe	[%]	18.0	18.1	17.9	18.0	18.0	18.1	18.1	18.1	18.1	18.1
Mo	[%]	2.9	2.9	2.9	2.8	2.8	2.8	2.9	2.8	2.8	2.8
Co	[%]	0.34	0.35	0.35	0.35	0.35	0.35	0.35	0.35	0.35	0.35
Cu	[%]	0.139	0.140	0.139	0.141	0.138	0.137	0.135	0.139	0.139	0.141
P	[%]	0.018	0.018	0.017	0.018	0.017	0.018	0.017	0.018	0.018	0.017
Sn	[ppm]	22	22	22	21	21	21	22	21	22	21
Ga	[ppm]	17.9	18.0	17.5	17.5	17.1	17.9	17.9	17.5	17.7	17.6
As	[ppm]	17.2	17.5	16.5	16.9	16.6	16.4	16.3	16.8	16.6	16.3
Sb	[ppm]	3.7	3.7	3.8	3.6	3.6	3.7	3.6	3.6	3.7	3.5
Pb	[ppm]	0.11	0.10	0.10	0.11	0.10	0.09	0.09	0.09	0.10	0.10
Bi	[ppm]	0.010	0.009	0.011	0.009	0.008	0.010	0.010	0.008	0.009	0.011

Repeat GD-MS analysis of NIST 1249 (Inconel 718)

Element	Unit	Average	STD	RSD
Ni	[%]	57.3	0.4	0.7%
Fe	[%]	18.0	0.07	0.4%
Mo	[%]	2.8	0.04	1.6%
Co	[%]	0.35	0.003	0.8%
Cu	[%]	0.139	0.002	1.2%
P	[%]	0.018	0.0005	2.6%
Sn	[ppm]	21.5	0.6	2.7%
Ga	[ppm]	17.7	0.3	1.6%
As	[ppm]	16.7	0.4	2.3%
Sb	[ppm]	3.7	0.1	2.5%
Pb	[ppm]	0.10	0.007	7.0%
Bi	[ppm]	0.009	0.001	10.5%

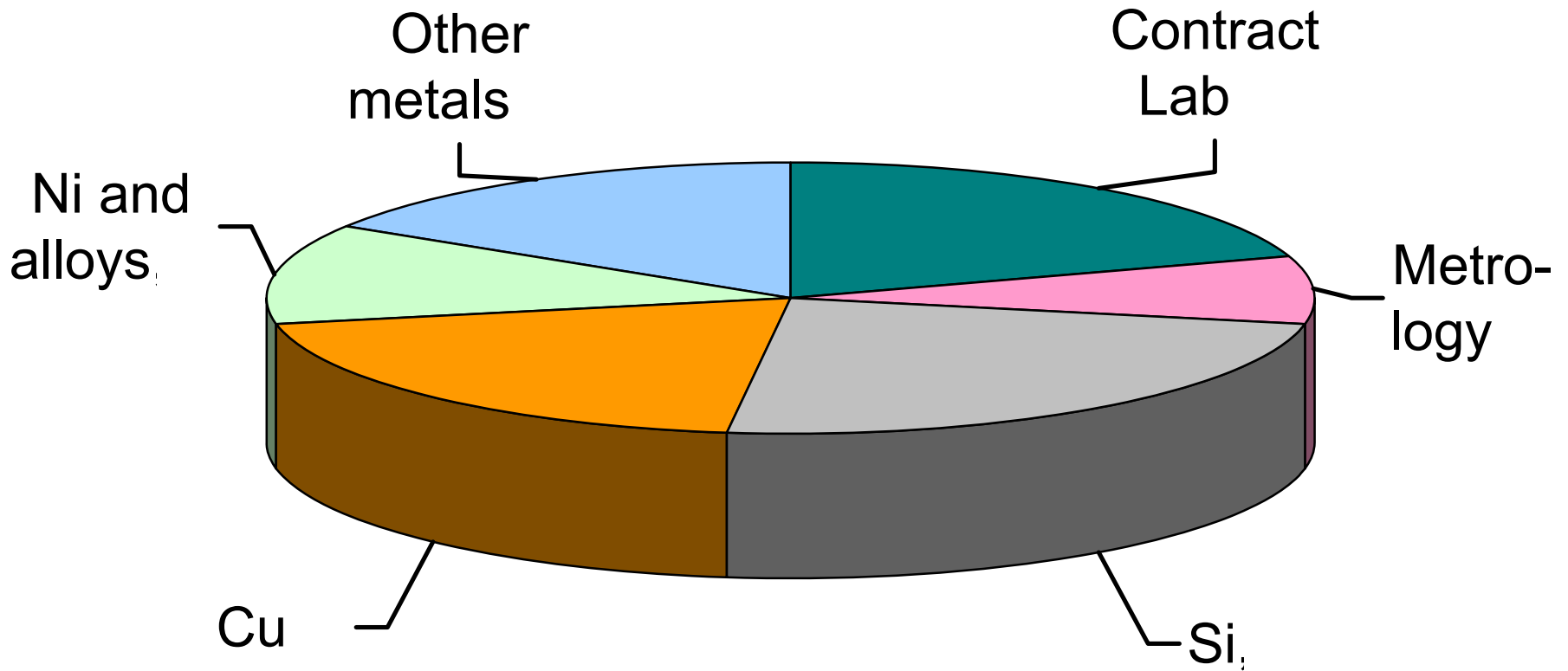
Ni alloys: Sensitivity ELEMENT XR vs ELEMENT GD

	ELEMENT XR [cps]	ELEMENT GD [cps]	GD-MS/ICP-MS
P	4527	199487	44
Co	194322891	13100000000	67
Cu	9648	766537	79
Ta	64270	775730	12
Pb	337	3369	10



ELEMENT GD by application

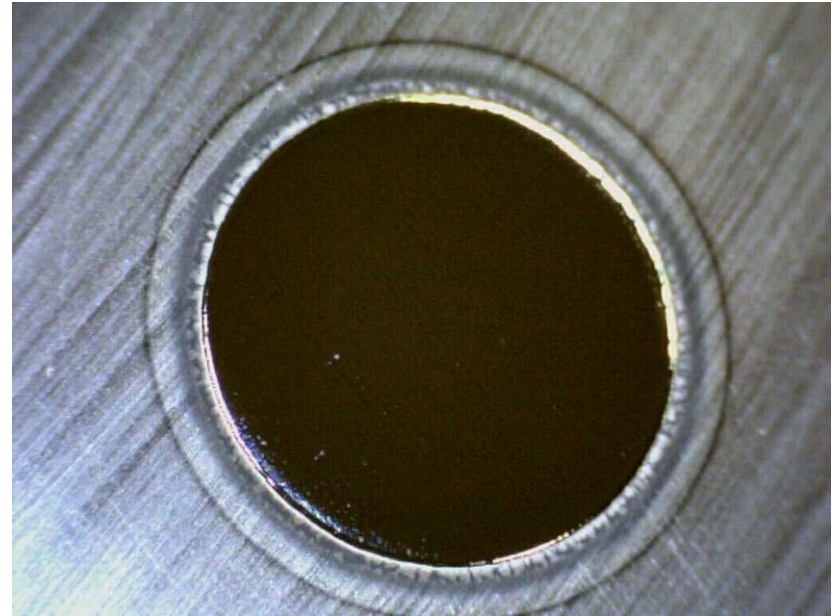
ELEMENT GD by application



Application examples Solar Cell Silicon

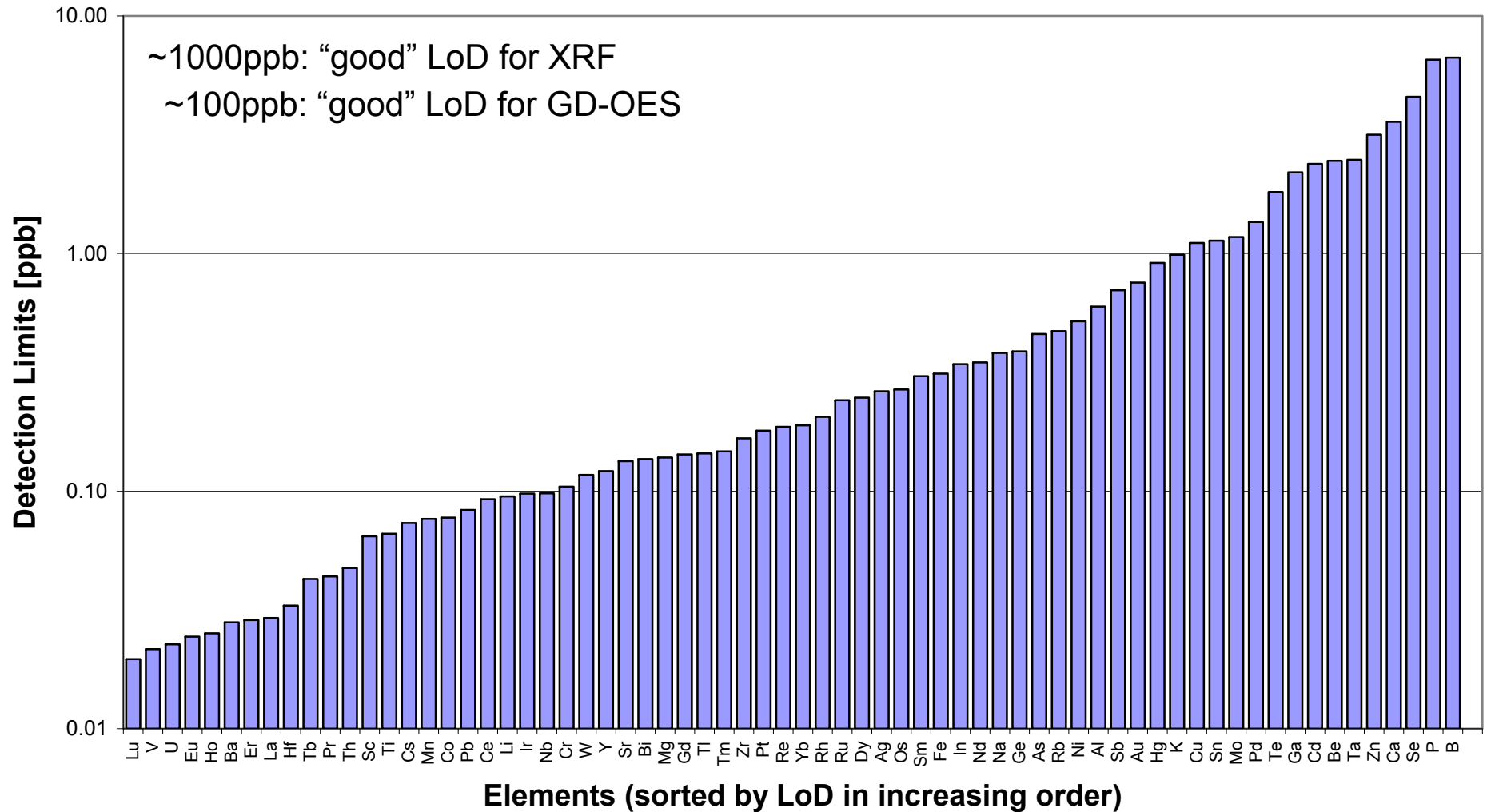
Challenges

- Routine determination of sub-ppm and sub-ppb concentrations
- High sputter yield required
- BEC & Memory
- Calibration
 - Mostly semiquant



GD-MS Analysis of Solar Cell Silicon

Detection limits (3s) in high purity Silicon sample (from 5 spots)



Special aspects of solid sampling at ppb level



Input from GD source parts: made from graphite

- High purity material available
- Very low sputter probability
- Lowest detection limits

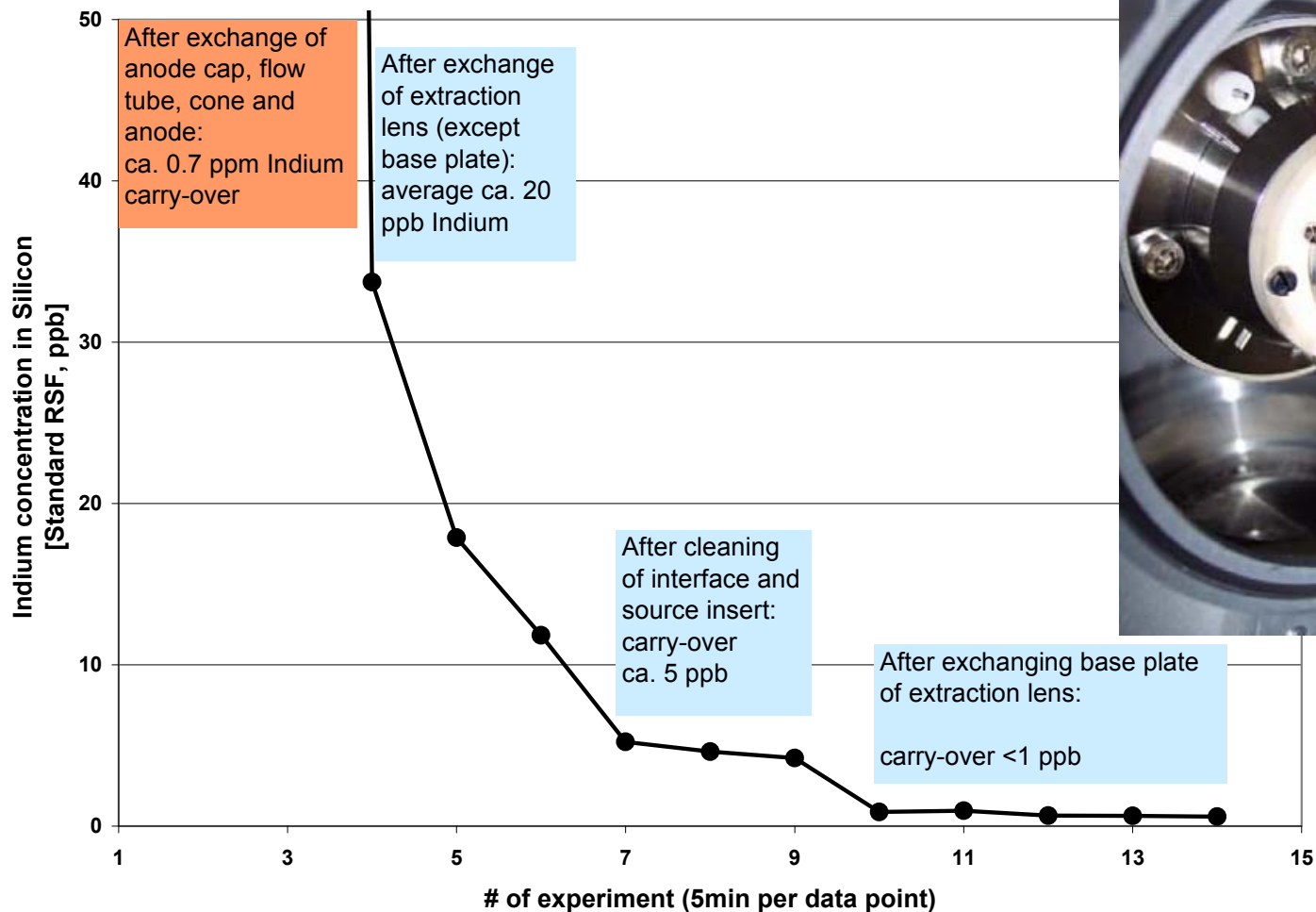


Input from Memory effects

- Experiment: Analyses of Si after sputtering of an In sample
- Finding: Major contribution (> 98 %) from deposits on extraction lens
- Solution: Plug-in extraction lens
 - Exchange by user within a few minutes through slide valve
 - Venting with Ar avoids moisture in vacuum system: instrument back in operation after 1.5 h



Tracking the source of memory effects



Input from previous sample: Plug-in cone

... and let it snap into position.



Mount clean cone
in holding ring...



Conclusion

- ELEMENT GD keeps HR-GDMS alive
 - Around 30 instruments within 4 years
 - Increasing demand from new markets, e.g. super alloys, solar cell industry
- ELEMENT GD is fast
 - Became a routine tool with > 5-6 samples/hour
- ELEMENT GD is a routine and powerful technique
 - Accepted technique (e.g. contract labs)
 - Used for a variety of samples
 - Used for matrix to ultra-trace determination
 - Easy to use; software based on HR-ICP-MS software